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(54) **ISOLATION REGION FABRICATION FOR REPLACEMENT GATE PROCESSING**

(56) **References Cited**

U.S. PATENT DOCUMENTS

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6,803,278	B2	10/2004	Tran	
6,812,149	B1 *	11/2004	Wang et al. ....	H01L 21/761 257/E21.544
7,049,185	B2	5/2006	Ito	
7,052,937	B2	5/2006	Clevenger et al.	
7,525,173	B2	4/2009	Yang et al.	
7,569,887	B2	8/2009	Otsuki	
7,671,469	B2	3/2010	Lee et al.	
7,785,946	B2 *	8/2010	Haffner et al. ....	438/183
8,502,316	B2	8/2013	Fung et al.	
2005/0169052	A1	8/2005	Hsu et al.	
2005/0239242	A1	10/2005	Zhu et al.	

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**Related U.S. Patent Documents**

**FOREIGN PATENT DOCUMENTS**

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JP	2004288685	A	10/2004
JP	2005340461	A	12/2005

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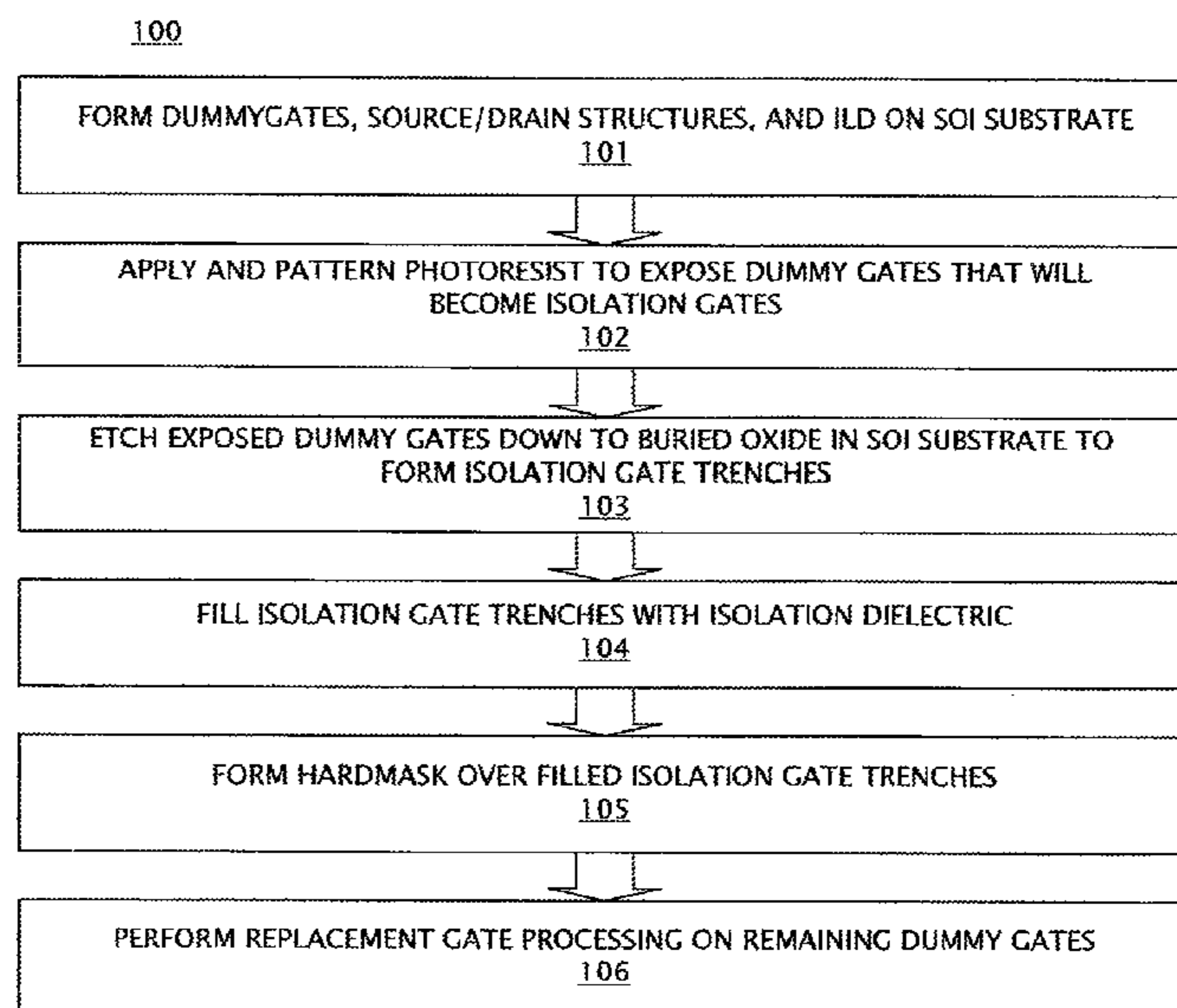
(57) **ABSTRACT**

A method for isolation region fabrication for replacement gate integrated circuit (IC) processing includes forming a plurality of dummy gates on a substrate; forming a block mask over the plurality of dummy gates, such that the block mask selectively exposes a dummy gate of the plurality of dummy gates; removing the exposed dummy gate to form an isolation region recess corresponding to the removed dummy gate; filling the isolation region recess with an insulating material to form an isolation region; removing the block mask to expose a remaining plurality of dummy gates; and performing replacement gate processing on the remaining plurality of dummy gates to form a plurality of active devices, wherein at least two of the plurality of active devices are electrically isolated from each other by the isolation region.

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**21/84** (2013.01); **H01L 27/1203** (2013.01)

(58) **Field of Classification Search**  
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See application file for complete search history.

**32 Claims, 9 Drawing Sheets**



(56)

**References Cited**

U.S. PATENT DOCUMENTS

2006/0125024 A1 6/2006 Ishigaki  
2008/0079088 A1 4/2008 Kudo  
2008/0197424 A1 8/2008 Haensch et al.  
2009/0114995 A1 5/2009 Suzuki et al.  
2010/0148248 A1 6/2010 Mikasa  
2010/0193877 A1 8/2010 Liaw et al.  
2011/0147765 A1 6/2011 Huang et al.

\* cited by examiner

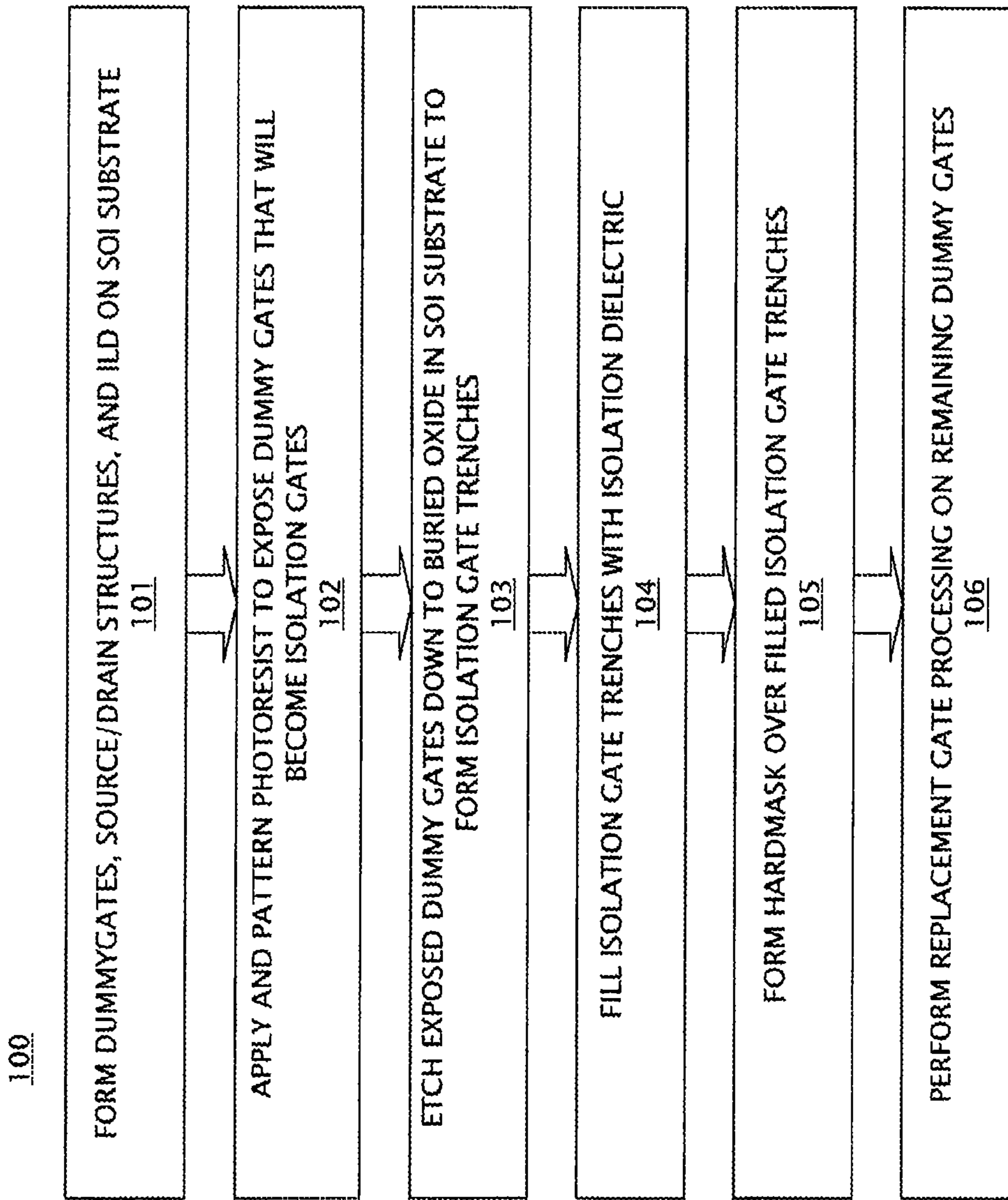


FIG. 1

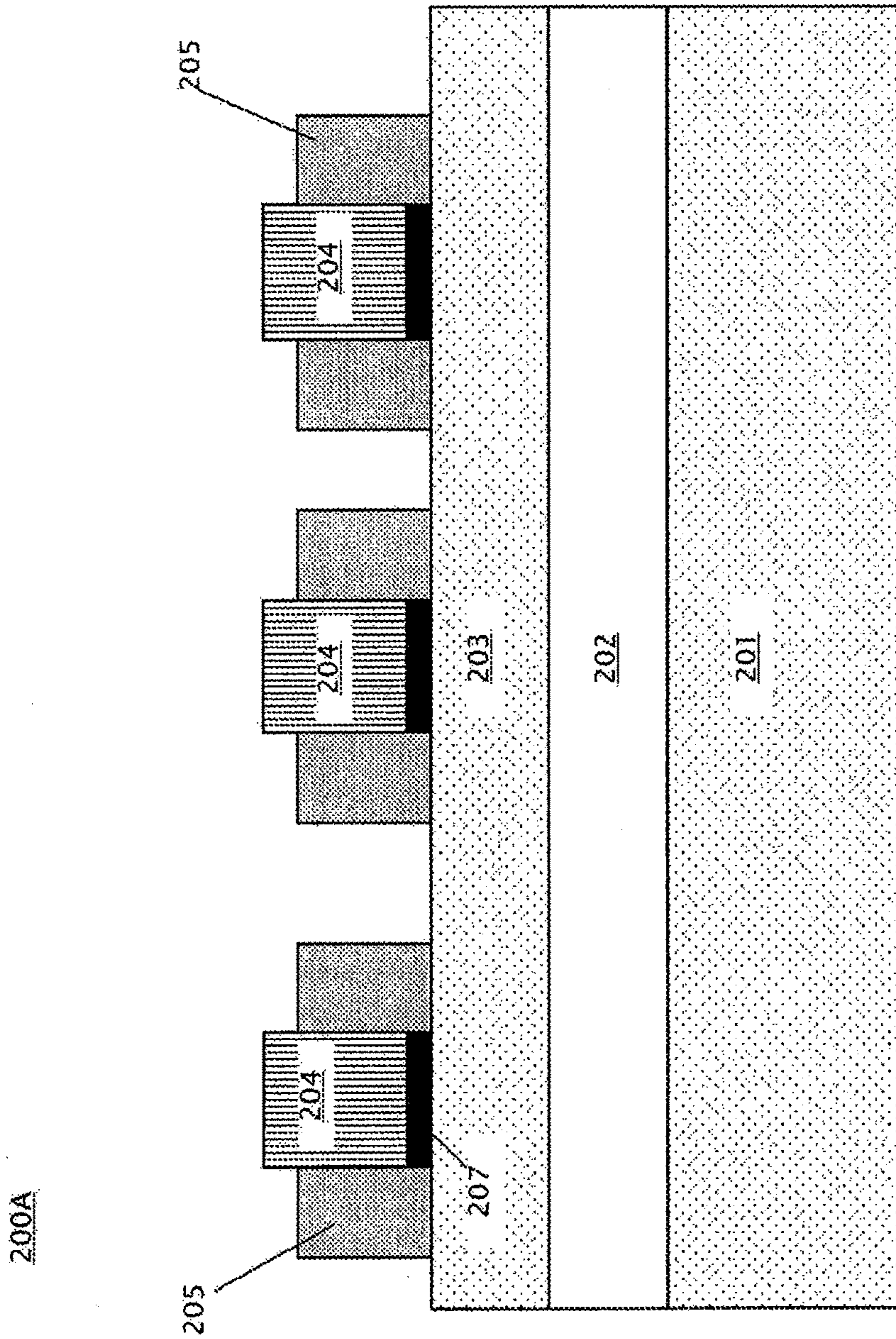


FIG. 2A

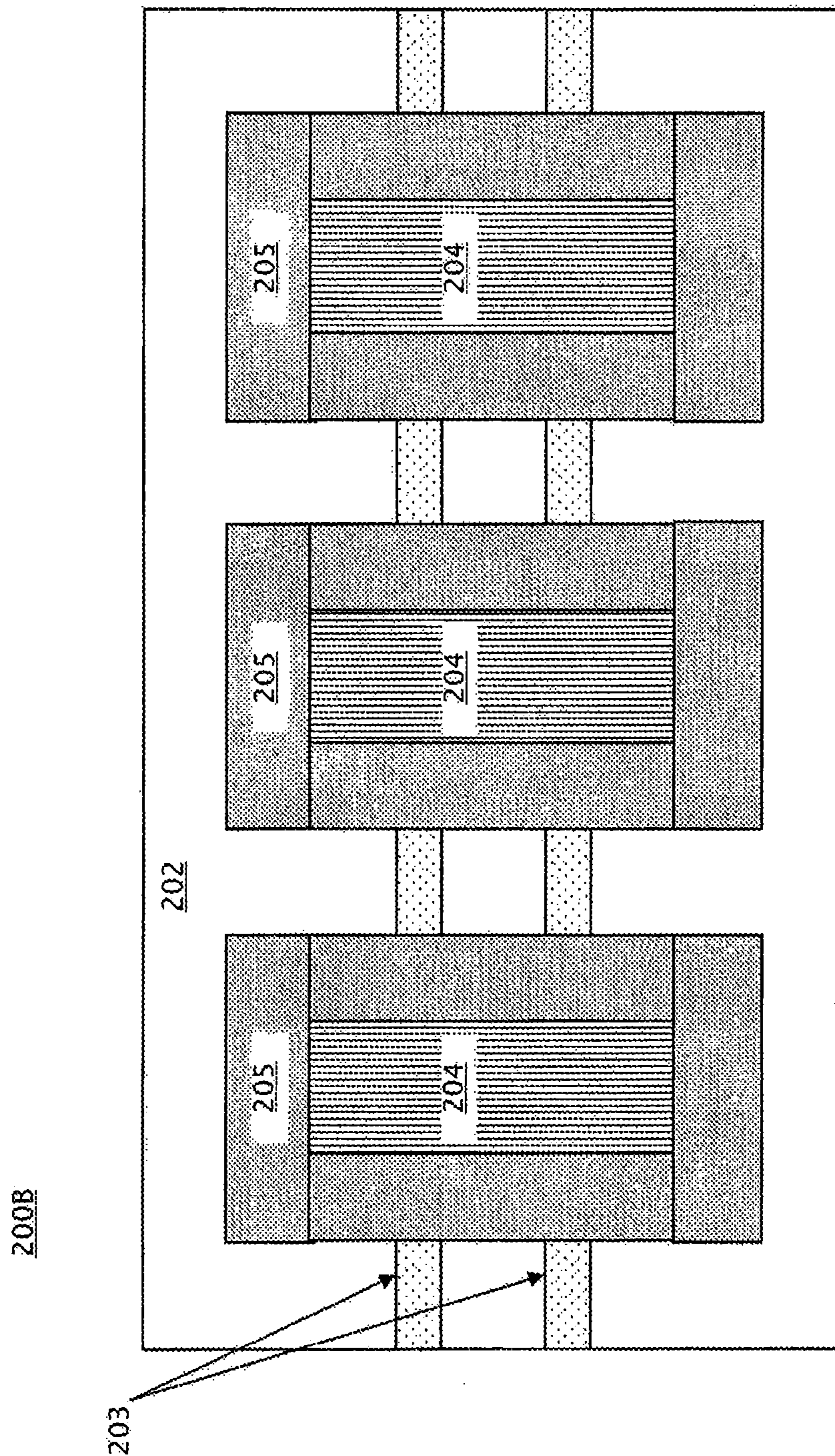


FIG. 2B

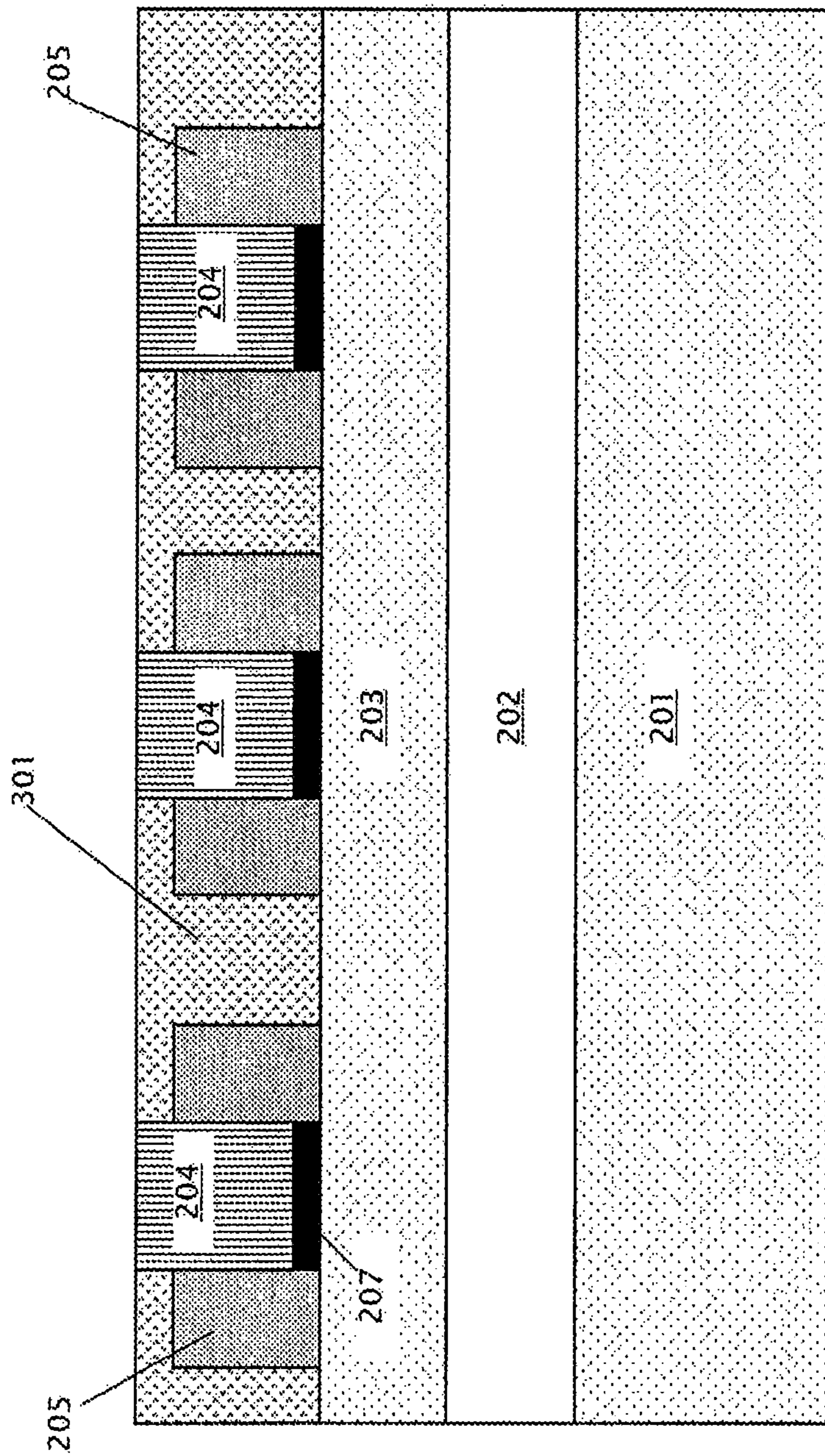


FIG. 3

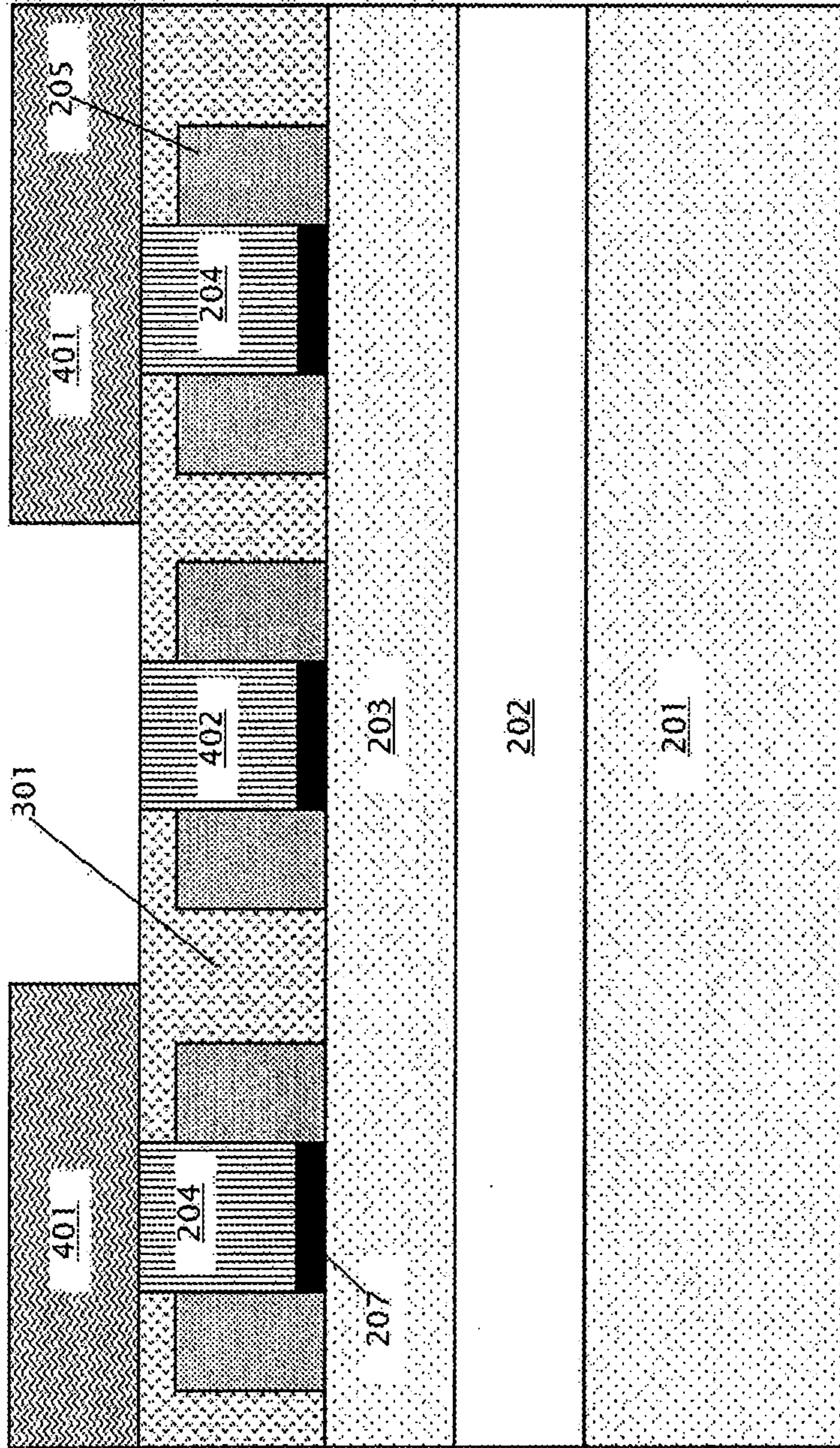


FIG. 4

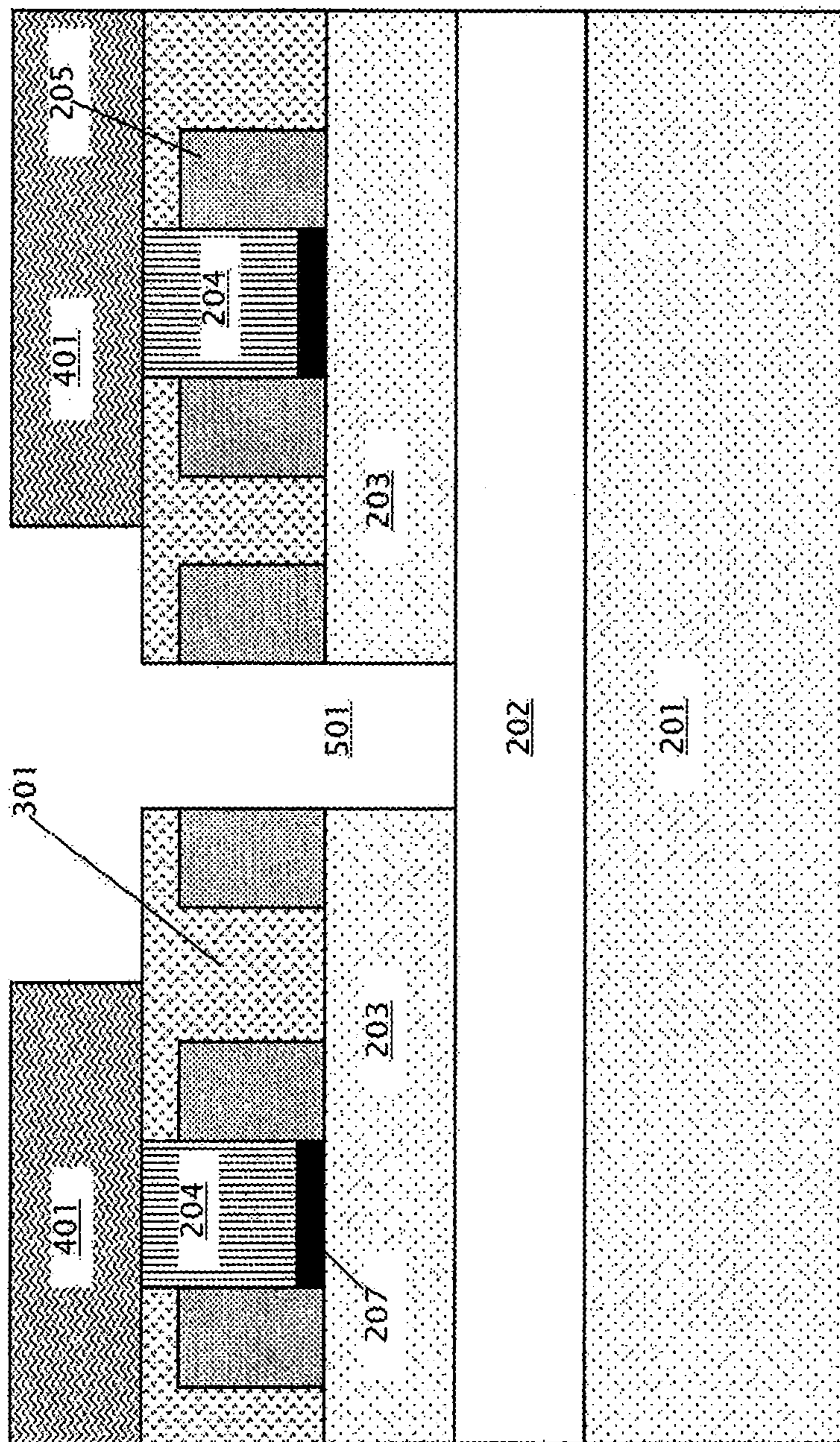


FIG. 5



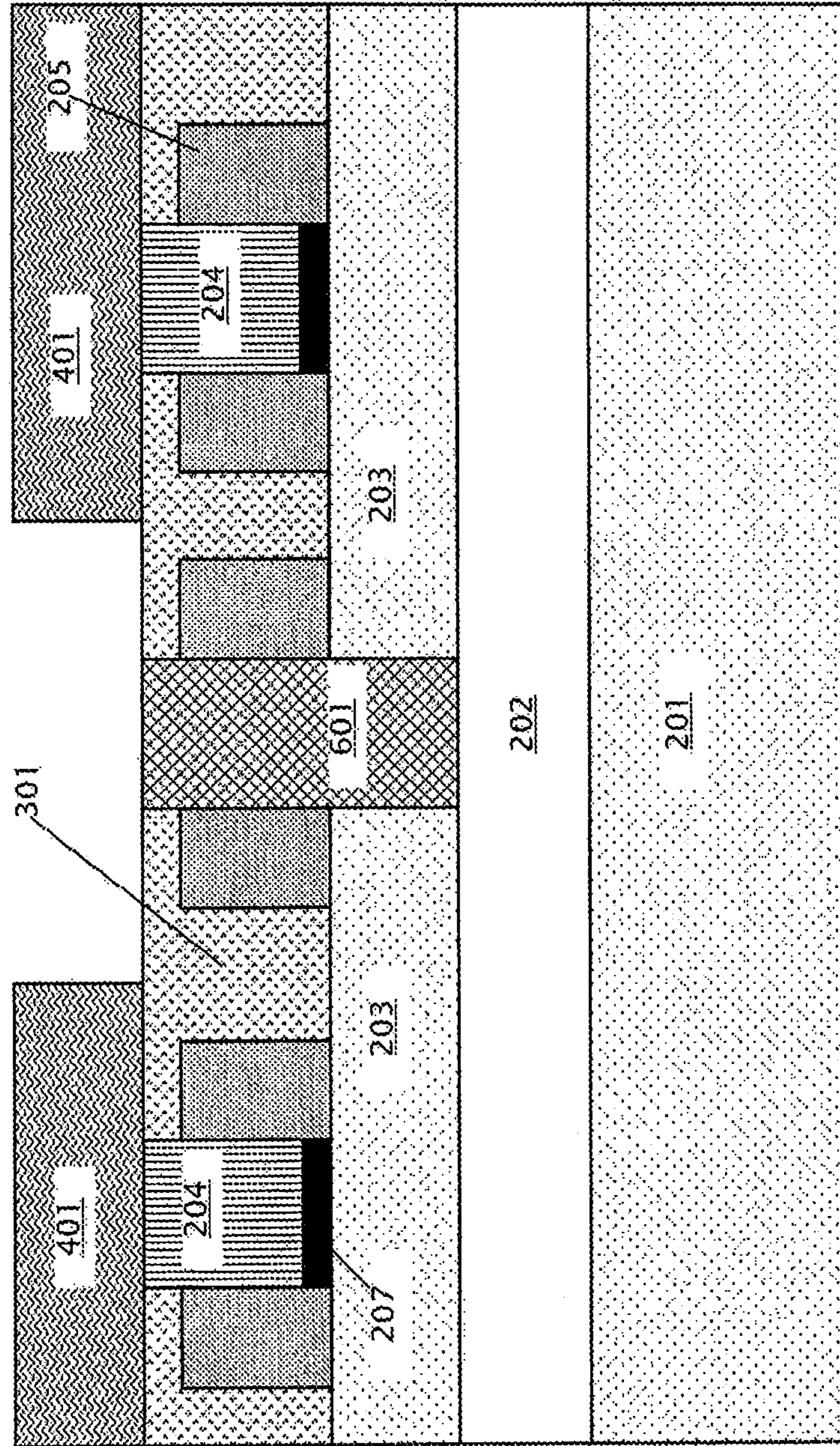


FIG. 6

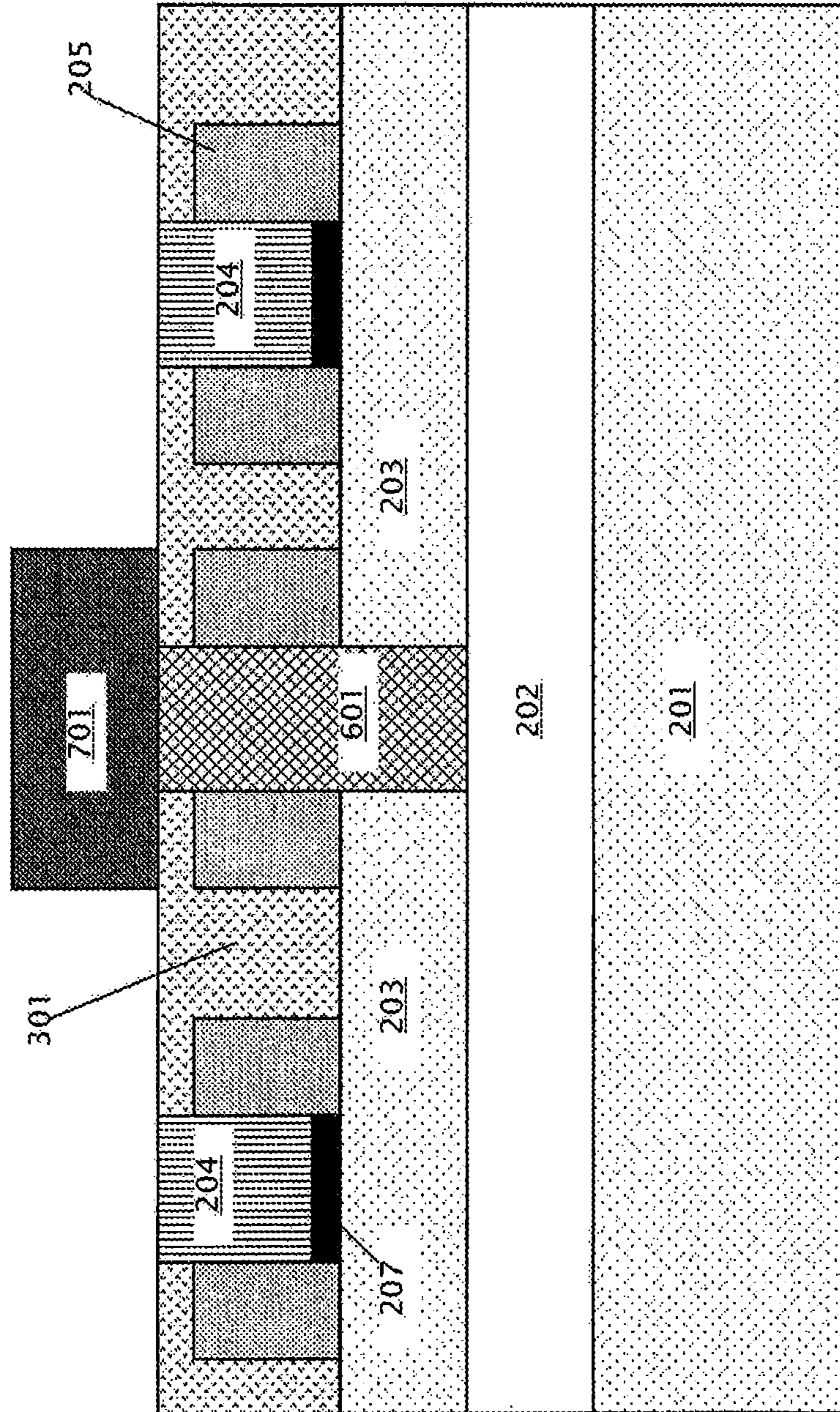


FIG. 7

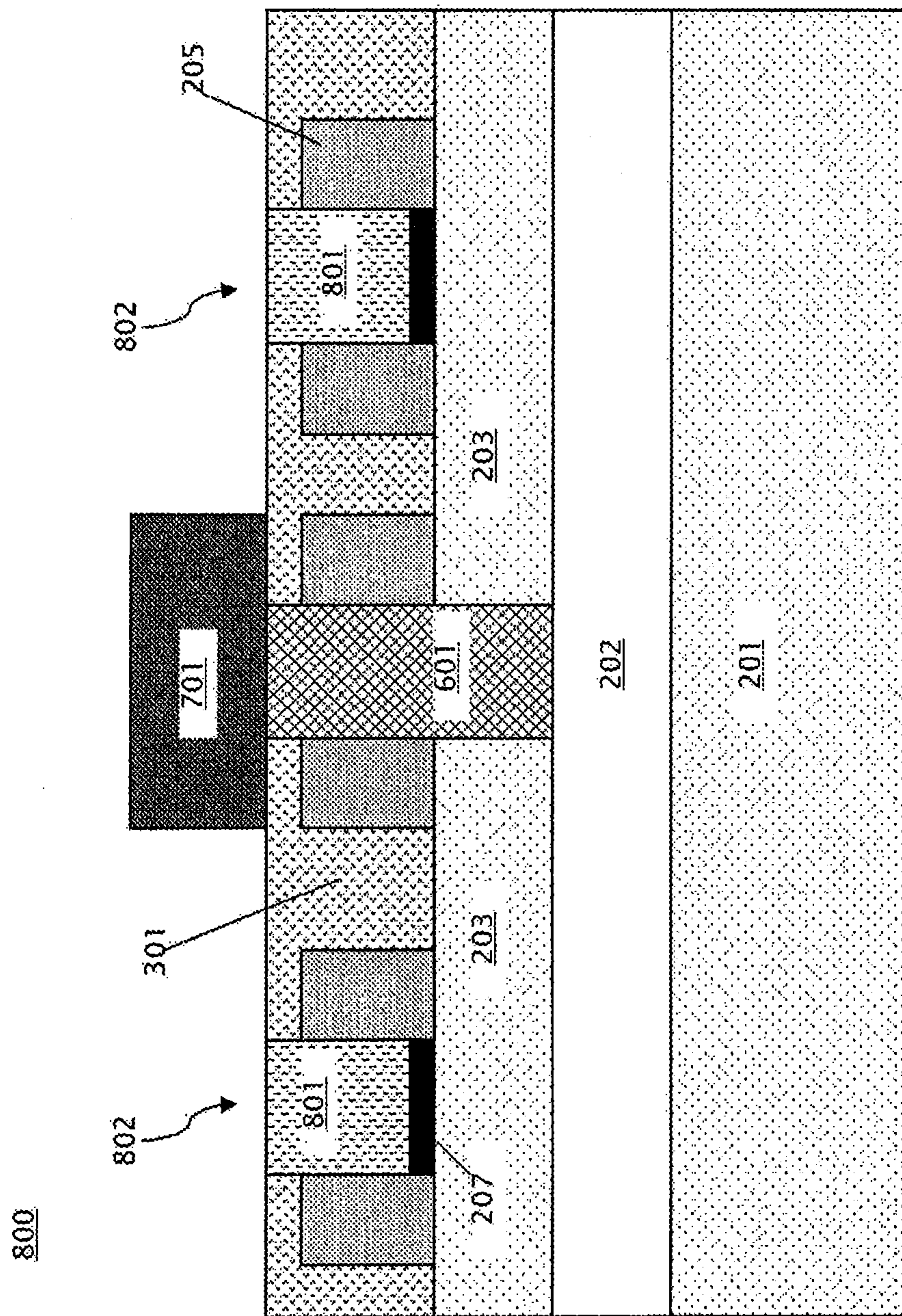


FIG. 8

## ISOLATION REGION FABRICATION FOR REPLACEMENT GATE PROCESSING

**Matter enclosed in heavy brackets [ ] appears in the original patent but forms no part of this reissue specification; matter printed in italics indicates the additions made by reissue; a claim printed with strikethrough indicates that the claim was canceled, disclaimed, or held invalid by a prior post-patent action or proceeding.**

### BACKGROUND

This disclosure relates generally to the field of integrated circuit (IC) manufacturing, and more specifically to isolation region fabrication for electrical isolation between semiconductor devices on an IC.

ICs are formed by connecting isolated active devices, which may include semiconductor devices such as field effect transistors (FETs), through specific electrical connection paths to form logic or memory circuits. Therefore, electrical isolation between active devices is important in IC fabrication. Isolation of FETs from one another is usually provided by shallow trench isolation (STI) regions located between active silicon islands. An STI region may be formed by forming a trench in the substrate between the active devices by etching, and then filling the trench with an insulating material, such as an oxide. After the STI trench is filled with the insulating material, the surface profile of the STI region may be planarized by, for example, chemical mechanical polishing (CMP).

However, use of raised (or regrown) source/drain structures, which may be employed to achieve lower series resistances of the IC or to strain FET channels, may exhibit significant growth non-uniformities at the boundary between a gate and an STI region, or when the opening in which the source/drain structure is formed is of variable dimensions. This results in increased variability in FET threshold voltage ( $V_t$ ), delay, and leakage, which in turn degrades overall product performance and power. One solution to such boundary non-uniformity is to require all STI regions to be bounded by isolation regions. However, inclusion of such isolation region structures may limit space available for wiring, device density, and increase the load capacitance, thereby increasing switching power of the IC.

### BRIEF SUMMARY

In one aspect, a method for isolation region fabrication for replacement gate integrated circuit (IC) processing includes forming a plurality of dummy gates on a substrate; forming a block mask over the plurality of dummy gates, such that the block mask selectively exposes a dummy gate of the plurality of dummy gates; removing the exposed dummy gate to form an isolation region recess corresponding to the removed dummy gate; filling the isolation region recess with an insulating material to form an isolation region; removing the block mask to expose a remaining plurality of dummy gates; and performing replacement gate processing on the remaining plurality of dummy gates to form a plurality of active devices, wherein at least two of the plurality of active devices are electrically isolated from each other by the isolation region.

In another aspect, a semiconductor structure, includes a silicon-on-insulator (SOI) substrate, the SOI substrate comprising a bottom silicon layer, a buried oxide (BOX) layer, and a top silicon layer; a plurality of active devices formed

on the top silicon layer; and an isolation region located between two of the active devices, wherein at least two of the plurality of active devices are electrically isolated from each other by the isolation region, and wherein the isolation region extends through the top silicon layer to the BOX layer.

Additional features are realized through the techniques of the present exemplary embodiment. Other embodiments are described in detail herein and are considered a part of what is claimed. For a better understanding of the features of the exemplary embodiment, refer to the description and to the drawings.

### BRIEF DESCRIPTION OF THE SEVERAL VIEWS OF THE DRAWINGS

Referring now to the drawings wherein like elements are numbered alike in the several FIGURES:

FIG. 1 illustrates a flowchart of an embodiment of a method of isolation region fabrication for replacement gate processing.

FIG. 2A is a cross sectional view illustrating an embodiment of a semiconductor structure including dummy gates on a silicon-on-insulator (SOI) substrate.

FIG. 2B is a top view illustrating an embodiment of the semiconductor structure of FIG. 2A that comprises fins for formation of fin field effect transistors (finFETs).

FIG. 3 is a cross sectional view illustrating the semiconductor structure of FIG. 2A after formation of an interlevel dielectric layer (ILD) over the dummy gates.

FIG. 4 is a cross sectional view illustrating the semiconductor structure of FIG. 3 after application and patterning of photoresist.

FIG. 5 is a cross sectional view illustrating the semiconductor structure of FIG. 3 after removal of an exposed dummy gate to form an isolation region trench.

FIG. 6 is a cross sectional view illustrating the semiconductor structure of FIG. 4 after removal filling the isolation region trench with an isolation dielectric.

FIG. 7 is a cross sectional view illustrating the semiconductor structure of FIG. 5 after formation of a hardmask layer over the isolation region trench.

FIG. 8 is a cross sectional view illustrating the semiconductor structure of FIG. 6 after replacement gate processing.

### DETAILED DESCRIPTION

Embodiments of a method for isolation region fabrication for replacement gate processing, and an IC including isolation regions, are provided, with exemplary embodiments being discussed below in detail. Instead of placing isolation regions at STI region boundaries, isolation regions may replace STI regions, as is described in U.S. patent application Ser. No. 12/951,575 (Anderson et al.), filed Nov. 22, 2010, which is herein incorporated by reference in its entirety. A relatively dense, low-capacitance IC may be formed by replacement gate (i.e., gate-last) processing through use of a block mask that selectively allows removal of active silicon in a gate opening to form an isolation region. The active silicon is removed in a manner that is self-aligned to the dummy gate, such that there is no overlap of gate to active area and hence minimal capacitance penalty.

FIG. 1 shows a flowchart of an embodiment of a method 100 of isolation region fabrication for replacement gate processing. FIG. 1 is discussed with reference to FIGS. 2-7. First, in block 101 of FIG. 1, a semiconductor structure

including dummy gates, source/drain regions, spacers, is formed on a substrate using regular semiconductor processing techniques, and an interlevel dielectric layer (ILD) is formed over the dummy gates. The semiconductor structure may also include raised source/drain regions located on either side of the dummy gates underneath the spacers in some embodiments. The semiconductor structure may include any appropriate semiconductor structure that includes dummy gates, including but not limited to a fin field effect transistor (finFET) structure. An embodiment of such a semiconductor structure **200A** is shown in FIG. 2A. The substrate is a silicon-on-insulator substrate, including bottom silicon layer **201**, buried oxide (BOX) layer **202**, and top silicon layer **203**. Dummy gates **204** are located on top silicon layer **203**. In some embodiments, a gate dielectric layer **207** is formed underneath each dummy gate **204**. The dummy gate structure **204** may be polysilicon in some embodiments. The gate dielectric layer **207** may be any appropriate dielectric material, and in some embodiments may include a bottom dielectric layer and a top metal layer. Spacers **205** are formed on either side of the dummy gates **204**. FIG. 2B shows a top view of an embodiment of the semiconductor structure **200A** of FIG. 2A in which the top silicon layer **203** has been patterned to form fins for finFETs. In the semiconductor structure **200B** of FIG. 2B, the dummy gates **204** wrap around and cover the fins that comprise top silicon layer **203**. After formation of the dummy gates **204**, as shown in FIG. 3, ILD **301** is formed over the dummy gates **204** and spacers **205**, and ILD **301** is planarized such that the top surfaces of dummy gates **204** are exposed.

Returning to method **100**, in block **102**, a block mask is applied to the top surface of the dummy gates and the ILD, and the block mask is patterned to selectively expose the dummy gates that are to become isolation regions. The block mask may comprise, for example, photoresist. FIG. 4 shows an embodiment of the semiconductor structure **200A** after application and patterning of photoresist **401** to form the block mask, which exposes a dummy gate **402**. Then, turning again to method **100**, in block **103**, the exposed dummy gate is removed, and the portion of the top silicon layer located underneath the removed dummy gate is etched down to the BOX layer to form an isolation region recess. FIG. 5 shows an embodiment of a device including an isolation region recess **501**. The etch used to remove exposed dummy gate **402** and its respective gate dielectric layer **207**, and to form the recess **501** in top silicon layer **203**, may be a sequential multistage etch. The sequential multistage etch may have 3 or 4 different stages depending on the materials that make up dummy gate **204** and gate dielectric layer **207**. In embodiments in which the dummy gate **402** is polysilicon, dummy gate **402** may be removed using a dry etch such as a bromine-based etch. The respective gate dielectric layer **207** may next be removed using a wet etch, such as a hydrofluoric etch for example. In embodiments in which respective gate dielectric layer **207** includes a bottom dielectric layer and a top metal layer, the etch to remove the gate dielectric layer **207** may be a 2-stage etch. Then, the recess **501** may be formed in the top silicon layer **203** using a dry etch such as a bromine-based etch to etch down to BOX layer **202**.

Next, in method **100** of FIG. 1, in block **104**, the recess that was formed during the etch performed in block **103** is filled with an insulating material to form the isolation region, and the top surface of the insulating material is planarized such as is shown in FIG. 6. In FIG. 6, the recess **501** is filled with an insulator, and the top surface of the insulator is planarized, to form isolation region **601**. The insulator that

comprises isolation region **601** may include silicon dioxide or silicon nitride in various embodiments. Then, flow of method **100** proceeds to block **105**, in which a hardmask layer is formed over the isolation region and the photoresist is removed. FIG. 7 shows an embodiment of a hardmask layer **701** formed over the isolation region **601**. The hardmask layer **701** may be silicon nitride. The photoresist **401** is also removed to expose the top surfaces of the remaining dummy gates **204**.

Lastly, in block **106** of method **100** of FIG. 1, replacement gate processing is performed on the remaining dummy gates, resulting in an IC device including electrical devices separated by isolation regions. An example of an IC device **800** including an isolation region **601** between two active devices is shown in FIG. 7. Dummy gates **204** have been replaced with gate stacks **801** to form active FETs **802**, including gate stacks **801**, gate dielectric layer **207**, spacers **205**, and source/drain and channel regions located underneath the devices in the top silicon layer **203**. The active FETs **802** may include raised source/drain regions (not shown) located under the spacers **205** in some embodiments. The active FETs **802** are separated by the isolation region **601**, which extends down to BOX layer **202**, preventing electrical leakage between active FETs **802**. The hardmask layer **701** acts to protect the isolation region **601** during the replacement gate processing. The hardmask layer **701** may be left on the device **800** in some embodiments, or in other embodiments the hardmask layer **701** may be removed after replacement gate processing is completed. FIGS. 2A-8 are shown for illustrative purposes only; a device formed using method **100** may include any appropriate number, type, and layout of FETs separated by any appropriate number and layout of isolation regions. For example, in some embodiments, two active devices in a semiconductor structure may have two isolation regions located between the two active devices. Also, in some embodiments, the gate dielectric layer that is initially formed underneath the dummy gate may be replaced during the replacement gate processing. The finished active devices may comprise finFETs in some embodiments, or any other appropriate type of active device that may be formed by replacement gate processing in other embodiments.

The technical effects and benefits of exemplary embodiments include formation of an IC having relatively high device density and low capacitance through replacement gate processing.

The terminology used herein is for the purpose of describing particular embodiments only and is not intended to be limiting of the invention. As used herein, the singular forms “a”, “an”, and “the” are intended to include the plural forms as well, unless the context clearly indicates otherwise. It will be further understood that the terms “comprises” and/or “comprising,” when used in this specification, specify the presence of stated features, integers, steps, operations, elements, and/or components, but do not preclude the presence or addition of one or more other features, integers, steps, operations, elements, components, and/or groups thereof.

The corresponding structures, materials, acts, and equivalents of all means or step plus function elements in the claims below are intended to include any structure, material, or act for performing the function in combination with other claimed elements as specifically claimed. The description of the present invention has been presented for purposes of illustration and description, but is not intended to be exhaustive or limited to the invention in the form disclosed. Many modifications and variations will be apparent to those of ordinary skill in the art without departing from the scope and

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spirit of the invention. The embodiment was chosen and described in order to best explain the principles of the invention and the practical application, and to enable others of ordinary skill in the art to understand the invention for various embodiments with various modifications as are suited to the particular use contemplated.

The invention claimed is:

**1.** A method for isolation region fabrication for replacement gate integrated circuit (IC) processing, the method comprising:

forming a plurality of dummy gates on a substrate;  
forming a block mask over the plurality of dummy gates, such that the block mask selectively exposes a dummy gate of the plurality of dummy gates;  
removing the exposed dummy gate to form an isolation region recess corresponding to the removed dummy gate;  
filling the isolation region recess with an insulating material to form an isolation region;  
removing the block mask to expose a remaining plurality of dummy gates; and  
performing replacement gate processing on the remaining plurality of dummy gates to form a plurality of active devices, wherein at least two of the plurality of active devices are electrically isolated from each other by the isolation region.

**2.** The method of claim **1**, wherein the substrate comprises a silicon-on-insulator substrate comprising a bottom silicon layer, a buried oxide (BOX) layer located on the bottom silicon layer, and a top silicon layer located on the BOX layer, wherein the plurality of dummy gates are formed on the top silicon layer, and wherein the isolation region recess extends through the top silicon layer down to the BOX layer.

**3.** The method of claim **1**, wherein the insulating material comprises one of silicon dioxide and silicon nitride.

**4.** The method of claim **1**, wherein removing the exposed dummy gate to form the isolation region recess comprises a sequential multilevel etch.

**5.** The method of claim **4**, wherein the sequential multilevel etch comprises:

etching the exposed dummy gate using a first etch;  
etching a gate dielectric layer corresponding to the exposed dummy gate using a second etch; and  
etching a top silicon layer of the substrate down to a buried oxide (BOX) layer of the substrate using a third etch.

**6.** The method of claim **5**, wherein the exposed dummy gate comprises polysilicon, and the first etch comprises a bromine-based dry etch.

**7.** The method of claim **5**, wherein the second etch comprises a hydrofluoric etch.

**8.** The method of claim **5**, wherein the gate dielectric layer comprises a bottom dielectric layer located on the substrate, and a top metal layer located on the bottom dielectric layer, and wherein the second etch comprises a two-stage etch.

**9.** The method of claim **5**, wherein the third etch comprises a bromine-based dry etch.

**10.** The method of claim **1**, further comprising forming a hardmask layer over the isolation region before performing the replacement gate processing on the remaining plurality of dummy gates to form the plurality of active devices.

**11.** The method of claim **10**, further comprising removing the hardmask layer after formation of the plurality of active devices.

**12.** The method of claim **10**, wherein the hardmask layer comprises silicon nitride.

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**13.** The method of claim **1**, wherein the block mask comprises photoresist.

**14.** The method of claim **1**, wherein the isolation region extends between a pair of spacers that are located on the substrate on either side of the isolation region, and through an interlevel dielectric (ILD) layer that is located over the pair of spacers.

**15.** A method of manufacturing a semiconductor device, the method comprising:

forming a plurality of dummy gates on a substrate;  
forming an interlevel dielectric layer over the substrate including the plurality of dummy gates;  
forming a block mask over the plurality of dummy gates and over the interlevel dielectric layer, such that the block mask selectively exposes a dummy gate of the plurality of dummy gates;  
removing the exposed dummy gate to form an isolation region recess corresponding to the removed dummy gate;  
filling the isolation region recess with an insulating material to form an isolation region;  
removing the block mask to expose a remaining plurality of dummy gates; and  
performing replacement gate processing on the remaining plurality of dummy gates to form a plurality of active devices, wherein at least two of the plurality of active devices are electrically isolated from each other by the isolation region.

**16.** The method of claim **15**, further comprising: planarizing the interlevel dielectric layer to expose top surfaces of the plurality of dummy gates.

**17.** The method of claim **15**, wherein the isolation region extends through the interlevel dielectric layer.

**18.** The method of claim **15**, wherein forming the block mask comprises forming the block mask to expose a portion of the interlevel dielectric layer, and

wherein removing the exposed dummy gate comprises removing the exposed dummy gate using the block mask and the exposed portion of the interlevel dielectric layer as etching masks.

**19.** The method of claim **15** wherein the substrate includes a fin for a finFET.

**20.** The method of claim **15** further comprising: forming spacers on opposing side walls of the plurality of dummy gates beneath the interlevel dielectric layer.

**21.** The method of claim **20** wherein forming the block mask comprises forming the block mask so that the block mask selectively exposes the dummy gate of the plurality of dummy gates and a pair of the spacers thereon.

**22.** The method of claim **21** wherein filling the isolation region recess comprises forming the isolation region to extend through the pair of spacers and the interlevel dielectric layer.

**23.** The method of claim **15** further comprising: forming spacers on opposing side walls of the plurality of dummy gates.

**24.** The method of claim **15** wherein after performing the replacement gate processing a top surface of the interlevel dielectric layer is coplanar with top surfaces of the plurality of active devices.

**25.** A method for isolation region fabrication for replacement gate integrated circuit (IC) processing, the method comprising:

forming a plurality of dummy gates on a substrate;  
forming spacers on opposing side walls of the plurality of dummy gates;

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forming a block mask over the plurality of dummy gates, such that the block mask selectively exposes a dummy gate of the plurality of dummy gates, the exposed dummy gate having a pair of the spacers thereon;  
 removing the exposed dummy gate to form an isolation region recess corresponding to the removed dummy gate;  
 filling the isolation region recess with an insulating material to form an isolation region extending between the pair of spacers;  
 removing the block mask to expose remaining ones of the plurality of dummy gates; and  
 performing replacement gate processing on the remaining ones of the plurality of dummy gates to form a plurality of active devices, wherein at least two of the plurality of active devices are electrically isolated from each other by the isolation region.

26. The method of claim 25, wherein the substrate includes a fin for a finFET.

27. The method of claim 25, further comprising:  
 prior to forming the block mask, forming an interlevel dielectric layer over the substrate including the plurality of dummy gates; and  
 planarizing the interlevel dielectric layer to expose top surfaces of the dummy gates.

28. The method of claim 27, wherein the isolation region extends through the pair of spacers and the interlevel dielectric layer.

29. The method of claim 27, wherein forming the block mask comprises forming the block mask to expose a portion of the interlevel dielectric layer, and  
 wherein removing the exposed dummy gate comprises removing the exposed dummy gate using the block mask and the exposed portion of the interlevel dielectric layer as etching masks.

30. The method of claim 25 further comprising:  
 prior to forming the block mask, forming an interlevel dielectric layer over the substrate including the plurality of dummy gates; and

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wherein after performing the replacement gate processing a top surface of the interlevel dielectric layer is coplanar with top surfaces of the plurality of active devices.

31. A method of manufacturing a semiconductor device, the method comprising:  
 forming a plurality of dummy gates on a substrate;  
 forming a mask over the plurality of dummy gates, such that the mask selectively exposes a dummy gate of the plurality of dummy gates;  
 removing the exposed dummy gate to form an isolation region recess corresponding to the removed dummy gate;  
 depositing an insulating material in the isolation region recess to form an isolation region;  
 removing the mask to expose a remaining plurality of dummy gates; and  
 performing replacement gate processing on the remaining plurality of dummy gates to form a plurality of active devices, wherein at least two of the plurality of active devices are electrically isolated from each other by the isolation region.

32. A method of manufacturing a semiconductor device, the method comprising:  
 forming a plurality of dummy gates on a substrate;  
 removing a selected dummy gate from the plurality of dummy gates to form an isolation region recess corresponding to the selected dummy gate;  
 depositing an insulating material in the isolation region recess to form an isolation region;  
 exposing remaining ones of the plurality of dummy gates; and  
 performing replacement gate processing on the remaining ones of the plurality of dummy gates to form a plurality of active devices, wherein at least two of the plurality of active devices are electrically isolated from each other by the isolation region.

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